F m PTO-1449 Attorney Docket No. 0756-1961 Serial No. 09/295,607 U.S. Department of Commerce (Rev. 8-83) Patent and Trademark Office Applicant: Shunpei YAMAZAKI et al. INFORMATION DISCLOSURE STATEMENT Group: 2811 Filing Date: April 22, 1999 (Use several sheets if necessary) **U.S. PATENT DOCUMENTS** Class **Subclass Filing Date** Name **Document Number** Examiner (if appropriate) Initial SIPE Loke 09/15/92 Liu et al 5,147,826 SEP 0 5 2000 01/04/94 Fonash et al 5,275,851 07/28/92 Tokunaga 5,134,018 RADEMARK 4.057.895 11/15/77 Ghezzo 07/06/99 5,920,781 **Imoto** 07/08/86 Han et al 4,599,118 AVAILABLE COPY 11/03/98 5,830,787 Kim 08/04/81 Ihara et al 4,282,646 08/31/99 Yamazaki et al 5,946,561 Loke 02/25/92 Yamazaki et al 5,091,334 FOREIGN PATENT DOCUMENTS **Subclass Translation Document Number** Date Country Class Yes No Loke EP 0 474 289 A1 03/11/92 Europe **Abstract** 10/25/88 63-258063 Japan Abstract 08/17/87 62-188373 Japan **Abstract** oke 01/29/93 Japan 5-21763 OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) Hempel et al., "Needle-Like Crystallization of Ni Doped Amorphous Silicon Thin Films", Solid State Loke Communications, Vol. 85, No. 11, March 1993, pp. 921-924 Hayzelden et al., "In Situ Transmission Electron Microscopy Studies of Silicide-Mediated Crystallization of Amorphous Silicon", Appl. Phys. Lett., Vol. 60, No. 2, January 13, 1992, pp. 225-227 Dvurenchenskii et al., "Transport Phenomena in Amorphous Silicon Doped by Ion Implantation of 3d Metals", Phys. Stat. Sol. Vol. (a) 95, (1986), pp. 635-640 Crowder et al., "DMOS FET with Common Field and Channel Doping", IBM Technical Disclosure Bulletin, Vol. 20, No. 4, September 1977, pp. 1617-1621 Fathimulla et al., "Reactively rf Magnetron Sputttered AIN Films as Gate Dielectric", J. Appl. Phys., Vol. 54, No. 8, August 1983, pp. 4586-4589 Gerova, "Deposition of AIN Thin Films by Magnetron Reactive Sputtering", Thin Solid Films - Preparation and Loke Characterization, Vol. 81, (1981), pp. 201-205 9/28/00 **Date Considered** Examiner *EXAMINER: Initial if citation considered, whether r not citatin is in conformance with MPEP 609; Draw line thrugh citation if not in conformance

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Sheet _1_ of _1 U.S. Department of Comments Attorney Docket No. 0756-1961 Serial No. 09/295.607 F rm PTO-1449 (Rev. 8-83) Patent and Trademark Office Applicant: Shunpei YAMAZAKI et al. INFORMATION DISCLOSURE STATEMENT CORRECTED Filing Date: April 22, 1999 Group: 2811 (Use several sheets if necessary) **U.S. PATENT DOCUMENTS Filing Date** Date Name Class **Subclass Document Number Examiner** (if appropriate) Initial BEST AVAILABLE COPY **FOREIGN PATENT DOCUMENTS Document Number** Date Country Class Subclass **Translation** Yes Abstract Loke 11/14/86 61-256663 Japan OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) 9/28/00 Loke. **Date Considered Examiner** *EXAMINER: Initial if citation c nsidered, whether r not citati n is in conf rmance with MPEP 609; Draw line through JUN 0 5 2000 43

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